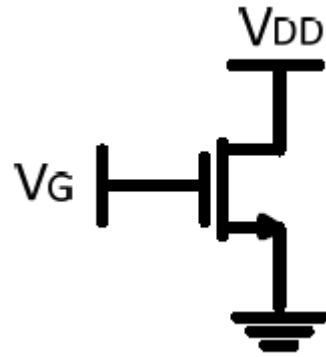
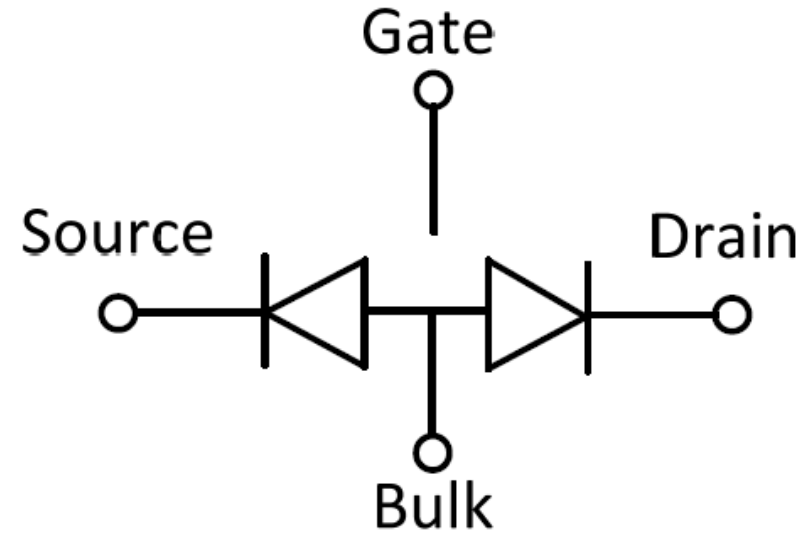
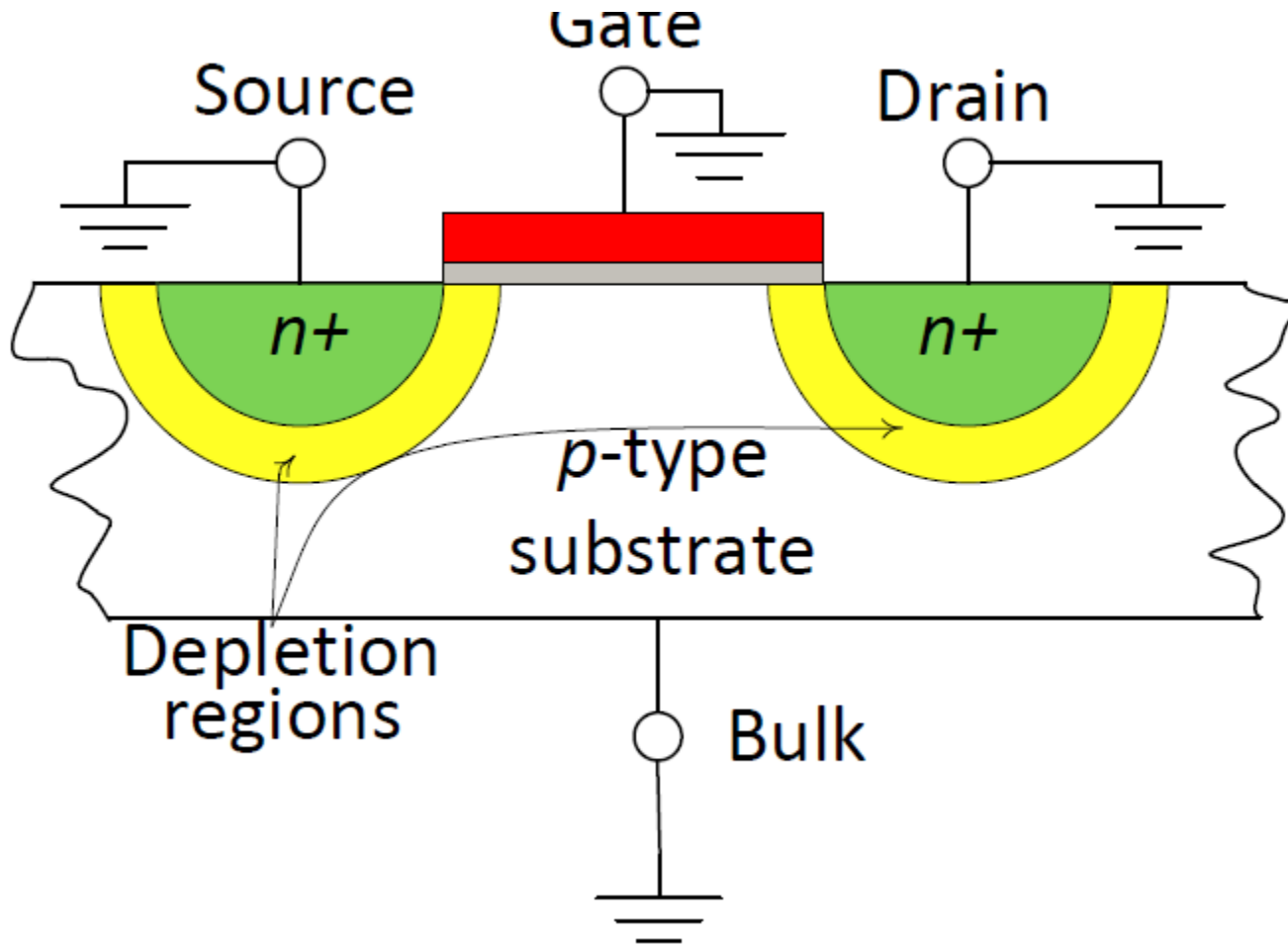


MOS Mode of operation

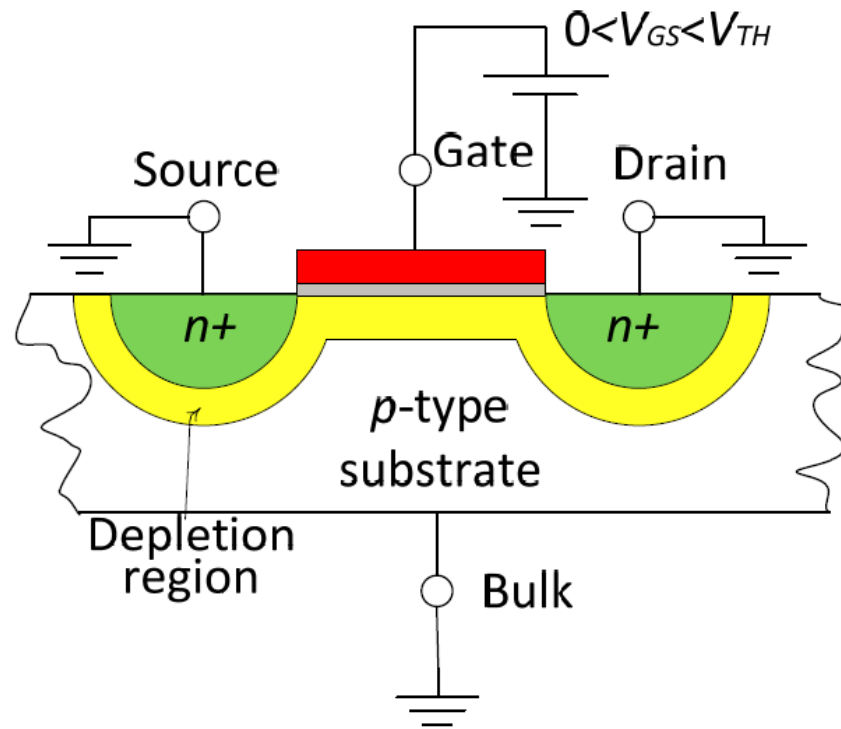


Equivalent circuit of an NMOS transistor with all terminals biased to ground



NMOS transistor with a $0 < V_{GS} < V_{TH}$.

- current cannot flow between Source and
- Drain, and the device is still in cut-off region.



Linear or triode region

- When $V_{GS} > V_{TH}$, the NMOS transistor is on, i.e. the conducting channel is formed, then a current flow
- between Source and Drain can exist.

$$I_{DS} = \frac{N \cdot q}{t_d} = \frac{Q_{ch}}{t_d}$$

$$Q_{ch} = C_{ox} \cdot L \cdot W \cdot (V_{GS} - V_{TH}) = C_{ox} \cdot L \cdot W \cdot V_{ov}$$

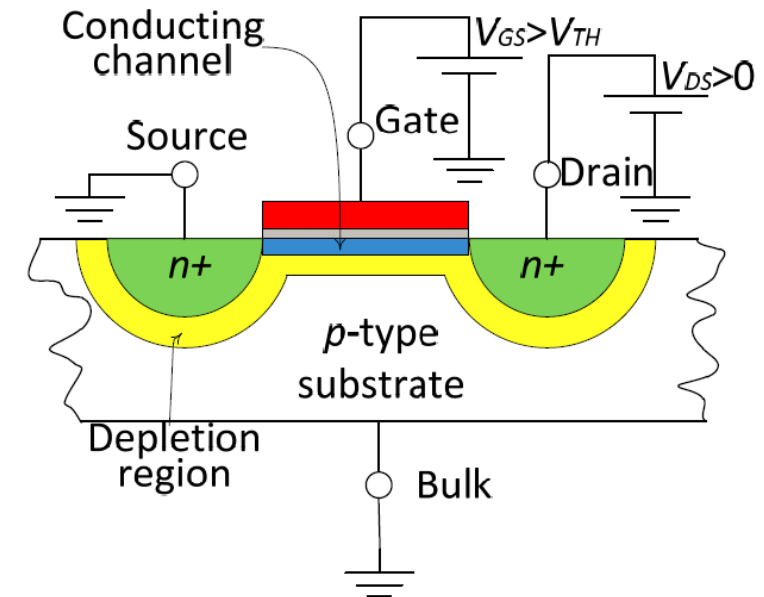
$$C_{ox} = \frac{\epsilon_{ox}}{t_{ox}}$$

$$t_{ox} = \frac{L_{min}}{50}$$

$$t_d = \frac{L}{v_d}$$

In standard CMOS technologies of the last twenty years t_{ox} is about fifty times lower than the minimum channel length L_{min}

Drift time, t_d , is directly proportional to the channel length L , and inversely proportional to the drift velocity of electrons, v_d ,



Linear or triode region

$v_d = \mu_n \cdot \epsilon_y$ • Drift velocity, v_d , is proportional to the horizontal electric field, ϵ_y ,

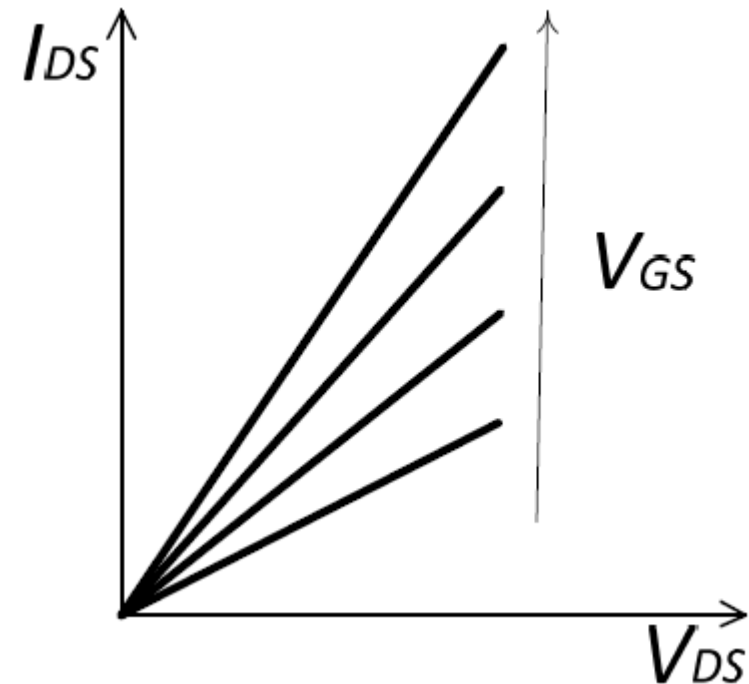
$\epsilon_y = \frac{V_{DS}}{L}$ • where μ_n is the electron mobility in the channel. The value of the horizontal electric field ϵ_y

$$I_{DS} = \mu_n \cdot C_{ox} \cdot \frac{W}{L} \cdot (V_{GS} - V_{TH}) \cdot V_{DS} = 2 \cdot k_n \cdot V_{ov} \cdot V_{DS}$$

$$k_n = \frac{1}{2} \cdot \mu_n \cdot C_{ox} \cdot \frac{W}{L}$$

the NMOS transistor acts like a variable resistance, R_{on} , whose value depends on V_{ov}

$$R_{on} = \frac{1}{2 \cdot k_n \cdot (V_{GS} - V_{TH})} = \frac{1}{2 \cdot k_n \cdot V_{ov}}$$



Linear or triode region

- a more accurate calculation of the channel charge is get by adding $V_{DS}/2$

$$Q_{ch} = C_{ox} \cdot L \cdot W \cdot \left(V_{GS} - V_{TH} - \frac{V_{DS}}{2} \right)$$

$$I_{DS} = \mu_n \cdot C_{ox} \cdot \frac{W}{L} \cdot \left(V_{GS} - V_{TH} - \frac{V_{DS}}{2} \right) \cdot V_{DS} = 2 \cdot k_n \cdot \left(V_{ov} - \frac{V_{DS}}{2} \right) \cdot V_{DS}$$

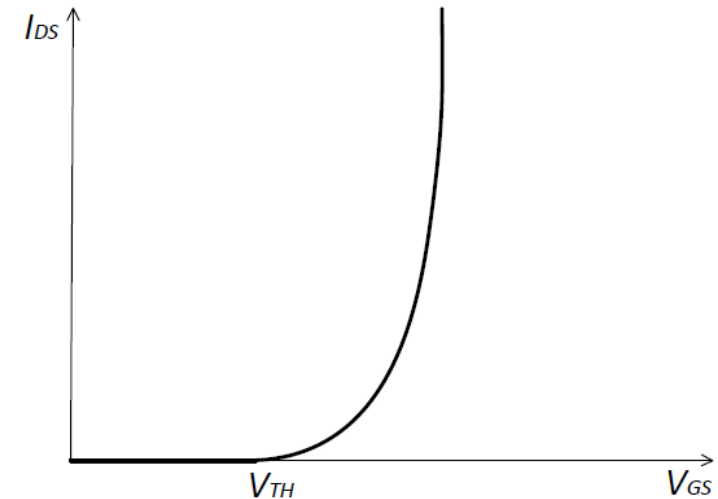
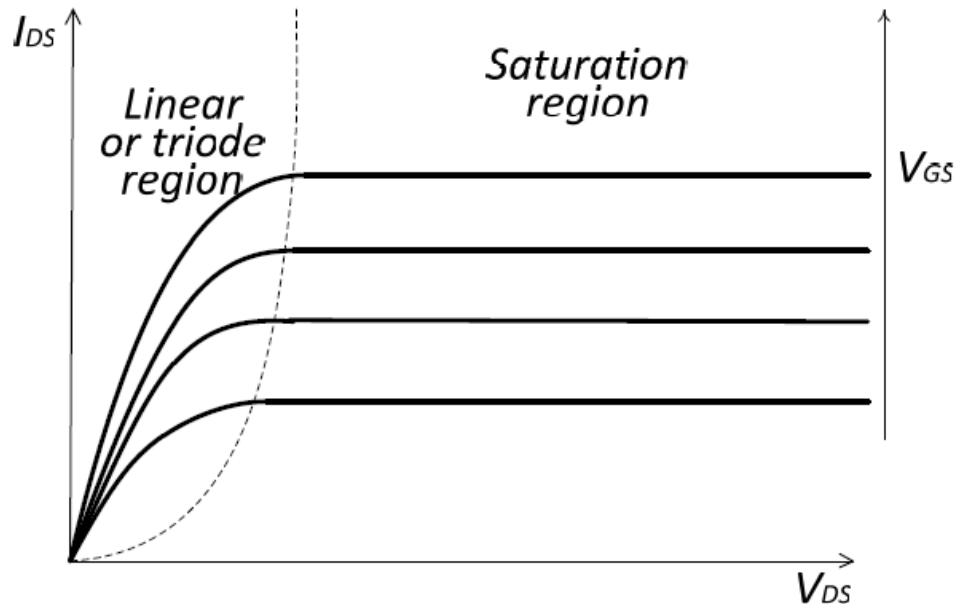
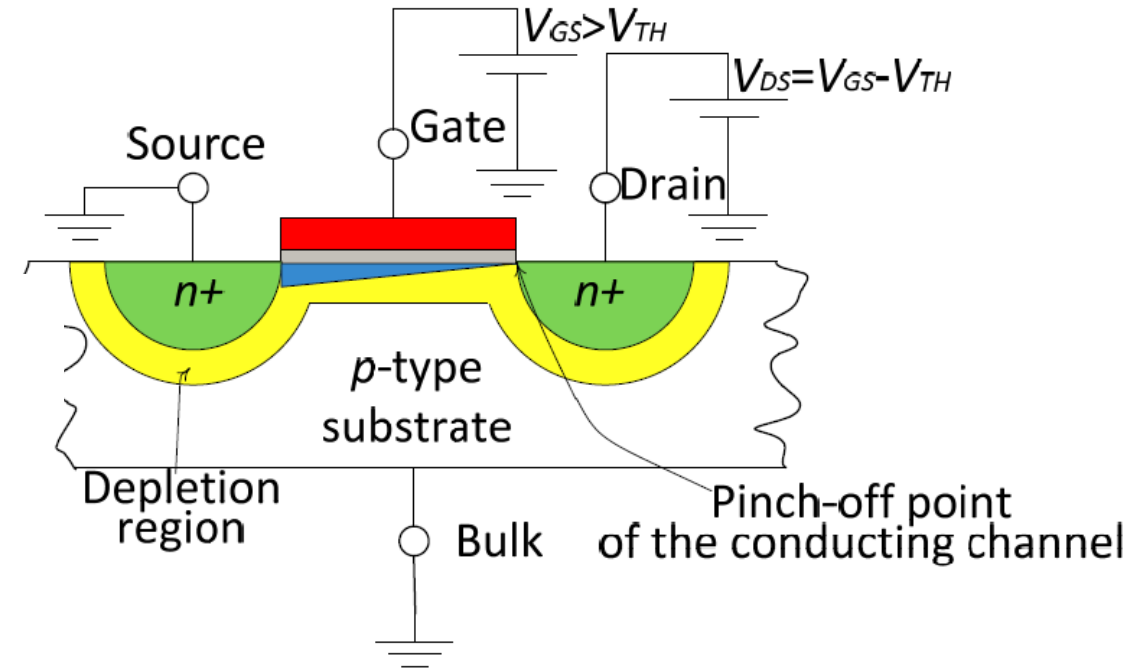
Saturation region

$$V_{GD} = V_{GS} - V_{DS} = V_{GS} - (V_{GS} - V_{TH}) = V_{TH}$$

$$I_{DS} = \frac{1}{2} \cdot \mu_n \cdot C_{ox} \cdot \frac{W}{L} \cdot (V_{GS} - V_{TH})^2 = k_n \cdot (V_{GS} - V_{TH})^2 = k_n \cdot V_{ov}^2$$

As V_{DS} approaches $V_{GS} - V_{TH}$, the channel charge approaches zero at the Drain end.

In fact, the channel charge is sustained by a Gate-Drain voltage, V_{GD} , at the drain side, which is less than V_{GS} at the Source side. When V_{DS} compensates for the overdrive voltage $V_{GS} - V_{TH}$, V_{GD} results to be equal to the threshold voltage V_{TH} .

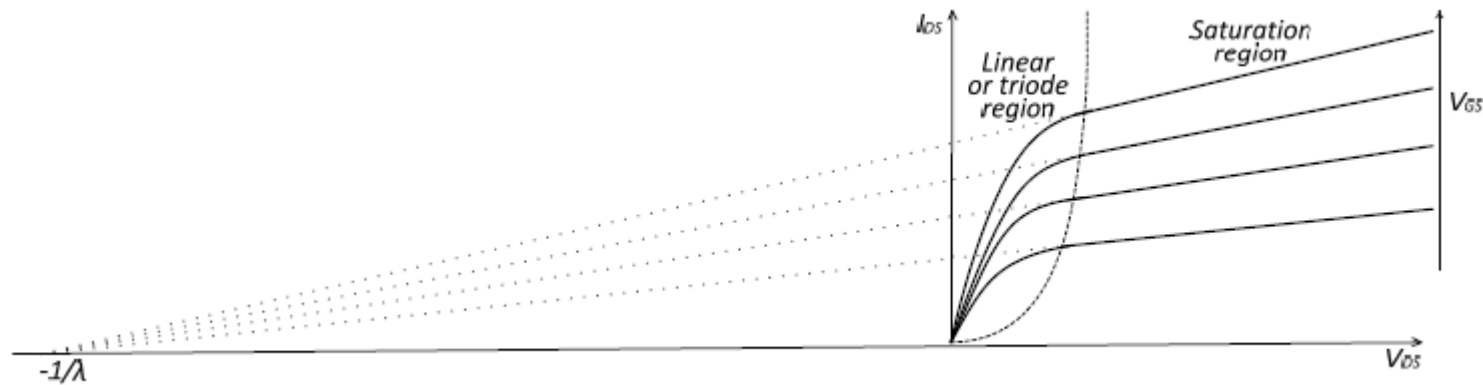


$I_{GS} - V_{GS}$ input characteristic of the NMOS transistor in saturation region

Saturation region

$$L_{eff} = L - \Delta L$$

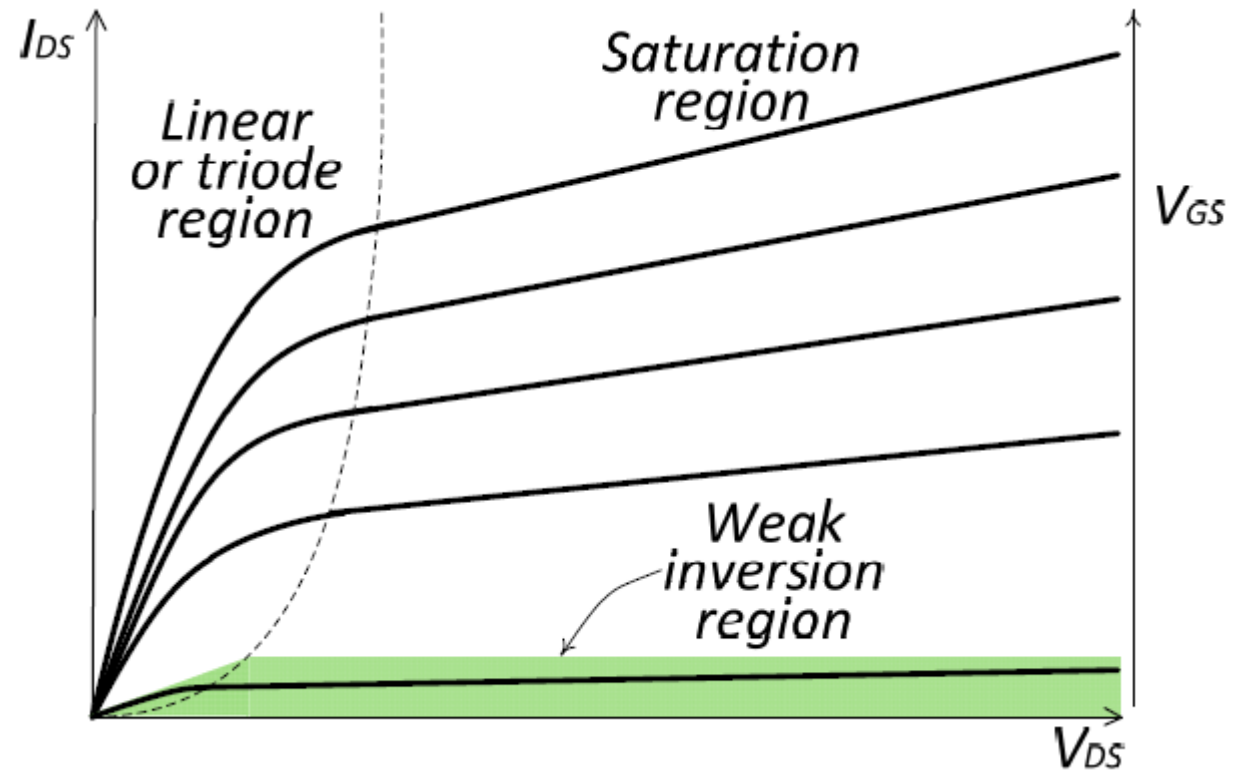
$$I_{DS} = \frac{1}{2} \cdot \mu_n \cdot C_{ox} \cdot \frac{W}{L_{eff}} \cdot (V_{GS} - V_{TH})^2$$



Weak inversion-leakage

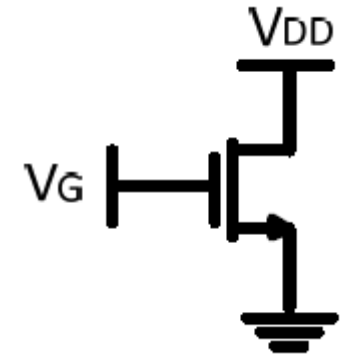
$$I_{DS} = I_S \cdot e^{\frac{V_{sur}}{V_t}}$$

$$I_{DS} = I_0 \cdot e^{nV_t}$$



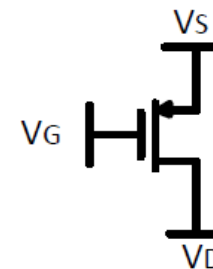
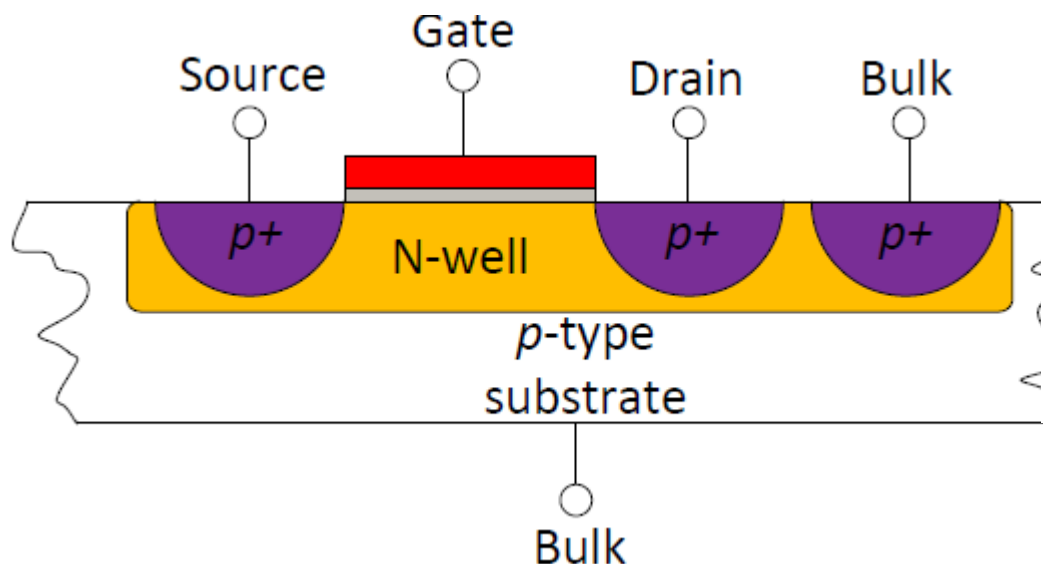
Summary for NMOS

Region of operation	Characteristic equation	V_{GS}	V_{DS}
Cut-off	$I_{DS}=0$	$<V_{TH}$	-
Linear or triode	$I_{DS} = \mu_n \cdot C_{ox} \cdot \frac{W}{L} \cdot \left(V_{GS} - V_{TH} - \frac{V_{DS}}{2} \right)$	$>V_{TH}$	$<V_{GS} - V_{TH}$
Saturation	$I_{DS} = \frac{1}{2} \cdot \mu_n \cdot C_{ox} \cdot \frac{W}{L} \cdot (V_{GS} - V_{TH})^2 \cdot (1 + \lambda \cdot V_{DS})$	$>V_{TH}$	$>V_{GS} - V_{TH}$
Weak inversion	$I_{DS} = I_0 \cdot e^{\frac{V_{GS}}{n \cdot V_t}}$	$\cong V_{TH}$	$>0 V$



Micrwind video: <https://youtu.be/MDARZD9OLNI>

PMOS



Region of operation	Characteristic equation	V_{SG}	V_{SD}
Cut-off	$I_{SD}=0$	$>V_{TH}$	-
Linear or triode	$I_{SD} = \mu_p \cdot C_{ox} \cdot \frac{W}{L} \cdot \left(V_{SG} + V_{TH} - \frac{V_{SD}}{2} \right) \cdot V_{SD}$	$<V_{TH}$	$>V_{SG} + V_{TH}$
Saturation	$I_{SD} = \frac{1}{2} \cdot \mu_p \cdot C_{ox} \cdot \frac{W}{L} \cdot (V_{SG} + V_{TH})^2 \cdot (1 + \lambda \cdot V_{SD})$	$<V_{TH}$	$<V_{SG} + V_{TH}$
Weak inversion	$I_{SD} = I_0 \cdot e^{\frac{V_{SG}}{n \cdot V_t}}$	$\cong V_{TH}$	$<0 V$

Region of operation	Characteristic equation	$ V_{GS} $	$ V_{DS} $
Cut-off	$ I_{DS} =0$	$< V_{TH} $	-
Linear or triode	$ I_{DS} = \mu_p \cdot C_{ox} \cdot \frac{W}{L} \cdot \left(V_{GS} - V_{TH} - \frac{ V_{DS} }{2} \right) \cdot V_{DS} $	$> V_{TH} $	$< V_{GS} - V_{TH} $
Saturation	$ I_{DS} = \frac{1}{2} \cdot \mu_p \cdot C_{ox} \cdot \frac{W}{L} \cdot (V_{GS} - V_{TH})^2 \cdot (1 + \lambda \cdot V_{DS})$	$> V_{TH} $	$> V_{GS} - V_{TH} $
Weak inversion	$ I_{DS} = I_0 \cdot e^{\frac{ V_{GS} }{n \cdot V_t}}$	$\cong V_{TH} $	$>0 V$

- cut-off;
- linear or triode;
- saturation;
- weak inversion.

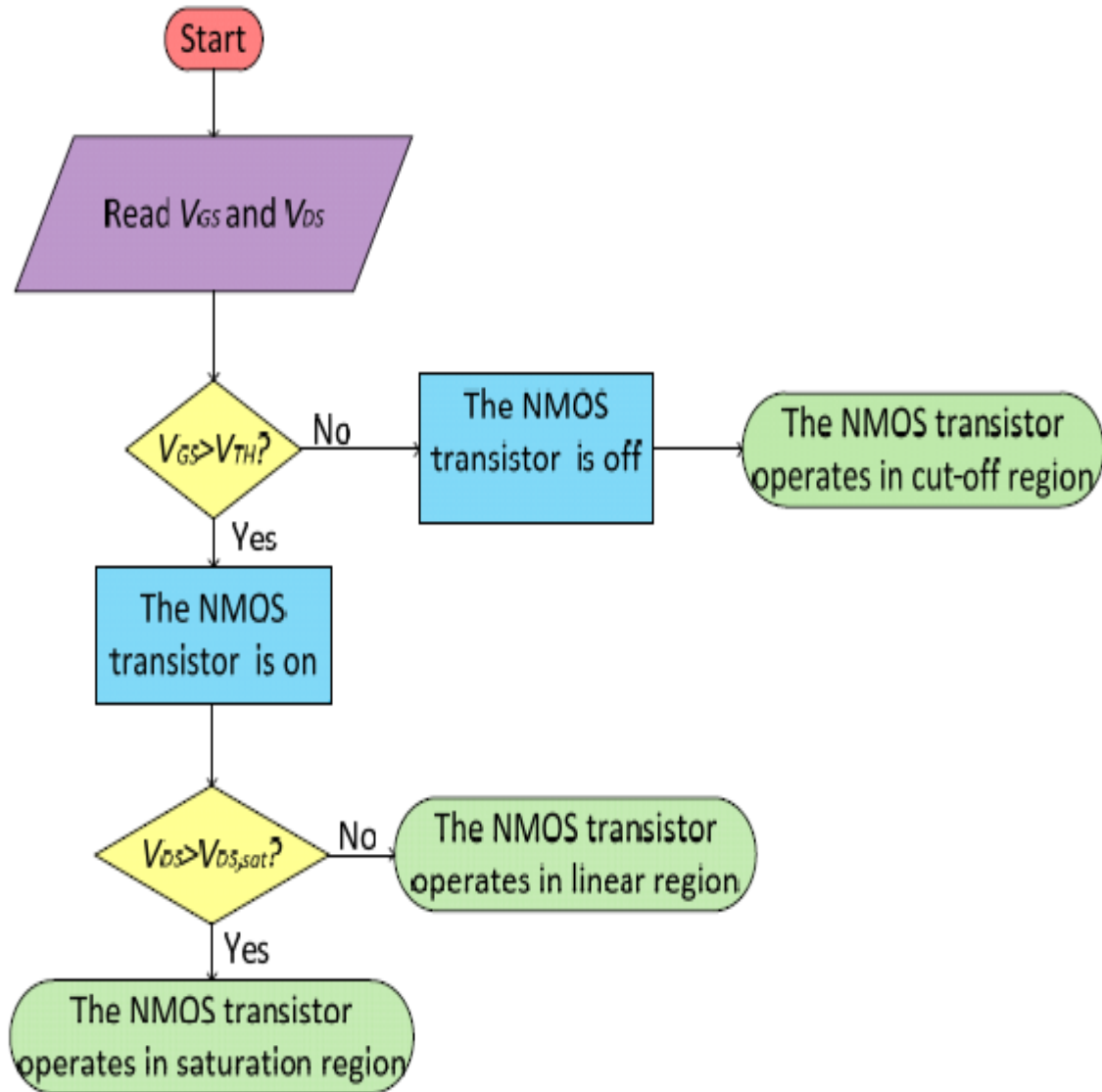
NMOS	PMOS
$I_{DS} \rightarrow I_{SD}$	
$V_{GS} \rightarrow V_{SG}$	
$V_{DS} \rightarrow V_{SD}$	
$V_{TH} \rightarrow -V_{TH}$	
$\mu_n \rightarrow \mu_p$	

$$\frac{\mu_n}{\mu_p} \cong 2.5$$

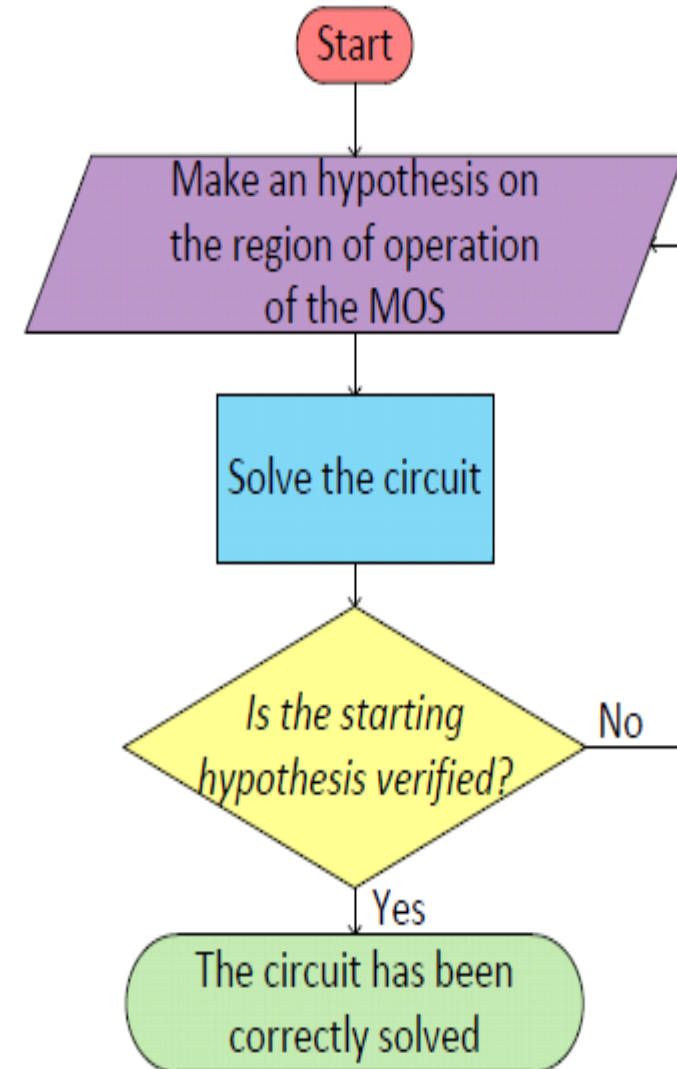
As in the PMOS transistor, I_{SD} is due to the drift of holes, the hole mobility, μ_p , has to be considered. The mobility of holes is quite less than electrons,

Therefore, a PMOS transistor has to be larger than a NMOS transistor in the same bias conditions in order to provide the same current.

NMOS transistor



Algorithm for solving a circuit including a MOS transistor by hand.



MOS REGIONS OF OPERATION

NMOS

CUTOFF : $V_{GS} < V_t$

$V_{GS} > V_t$

IF $V_{DS} > V_{GS} - V_t \rightarrow$ SATURATION

IF $V_{DS} < V_{GS} - V_t \rightarrow$ TRIODE / LINEAR

$V_{DS} - V_{GS} > -V_t$

$V_{GS} - V_{DS} < V_t$

$V_{GD} < V_t \rightarrow$ SATURATION

$V_{GD} > V_t \rightarrow$ TRIODE / LINEAR

PMOS

CUTOFF $V_{SG} < |V_t|$

$V_{SG} > |V_t|$

$V_{SD} > V_{SG} - |V_t| \rightarrow$ SATURATION

$V_{SD} < V_{SG} - |V_t| \rightarrow$ TRIODE / LINEAR